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(54) PRODUCTION OF HIGH RESISTANCE AMORPHOUS NiP FOIL STRIP OF LARGE WIDTH

(57)Abstract:

PURPOSE: To produce high resistance amorphous NiP foil of a large width by pulse electrolysis by depositing an NiP alloy on a substrate at a specified current density with a specified period of pulsation in a bath prepd. by mixing a Watts bath with an oxy-acid of phosphorus or a salt thereof and by stripping the resulting NiP alloy film.

CONSTITUTION: A bath prepd. by mixing a Watts bath with an oxy-acid of phosphorus or a salt thereof such as phosphorous acid, hypophosphorous acid or sodium hypophosphite is used. A pulsating current ip having 0.01W100msec on-time and off-time is supplied at a current density represented by the formula to deposit an NiP alloy on a substrate of an easily passivable and electrically conductive material. The resulting NiP alloy film is stripped from the substrate. Thus, high resistance amorphous NiP foil of large width is obtd.

10<1P<300A/Am